

Explanation of References

- 1... mask blanks
- 2... membrane
- 5 3... resist
- 4... beam
- 5... supporting frame portion
- 6... etching stopper layer
- 7... mask side alignment mark
- 10 8... protective film
- 11... alignment substrate
- 12... alignment mark
- 13... alignment mark supporting portion
- 13a... step portion
- 15 14... first silicon wafer (substrate)
- 15... etching stopper layer
- 16A... alignment light
- 16B... electron beam for alignment
- 17A... reflection light of alignment light
- 20 17B... reflection beam of electron beam for alignment
- 18A... light detector
- 18B... electron beam detector
- 21... second silicon wafer
- 22... alignment mask formation layer
- 25 23, 24... resist
- 101... membrane mask
- 102... membrane

- 103... absorbing material
- 104... beam
- 105... supporting frame portion
- 106... stencil mask
- 5 107... membrane
- 108... opening portion
- 109... etching stopper layer